Electronic Supplementary Information (ESI)

# Thin Film Field-effect Transistors of 2,6-diphenyl Anthracene (DPA)

Jie Liu,<sup>a,f</sup> Huanli Dong,<sup>a,h\*</sup> Zongrui Wang,<sup>a,f</sup> Deyang Ji,<sup>a,f</sup> Changli Cheng,<sup>e</sup> Hua Geng,<sup>a</sup> Hantang Zhang,<sup>a,f</sup>

Yonggang Zhen,<sup>a</sup> Lang Jiang,<sup>b</sup> Hongbing Fu,<sup>a</sup> Zhishan Bo,<sup>c</sup> Wei Chen,<sup>d</sup> Zhigang Shuai<sup>e\*</sup> and Wenping Hu<sup>a,g\*</sup>

<sup>a</sup> Beijing National laboratory for Molecular Sciences, Key Laboratory of Organic Solids, Institute of Chemistry, Chinese Academy of Sciences, Beijing 100190, China;

<sup>b</sup> Cavendish Laboratory, Cambridge University, JJ Thomson Avenue, Cambridge CB3 0HE, UK;

<sup>c</sup> Department of Chemistry, Beijing Normal University, Beijing 100875, China;

<sup>d</sup> Department of Chemistry, National University of Singapore, 3 Science Drive 3, 117543, Singapore;

<sup>e</sup> Department of Chemistry, Tsinghua University, Beijing 100084, China;

<sup>f</sup>University of the Chinese Academy of Sciences, Beijing 100039, China;

<sup>g</sup> Collaborative Innovation Center of Chemical Science and Engineering (Tianjin), Tianjin 300072, China;

<sup>h</sup> Department of Chemistry, Capital Normal University, Beijing, 100037.

\*Correspondence: <u>dhl522@iccas.ac.cn</u>; <u>zgshuai@tsinghua.edu.cn;huwp@iccas.ac.cn</u>

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Reference

#### **Experimental Section**

#### Materials and synthesis

All reagents and chemicals were obtained from commercial sources and used without further purification.

2,6-Diol-anthracene: To a 100 mL two neck round bottom flask fitted with magnetic bar, was added sodium borohydride (2.4 g, 62.5 mmol) and 1M sodium carbonate solution (60 mL). 2,6-dihydroxyanthracene-9,10-dione (1.2 g, 5 mmol) was added in small portions which resulted in colorless gas evolution. After gas evolution stopped, the whole system was heated up to 80 °C for 30 min. It was then transferred to a 500 mL baker fitted with magnetic bar and slowly acidified with 3M HCl (60 mL) and then filtrated and dried. The filtrate was washed on a filter with acetone and the solution was evaporated under reduced pressure to afford brown solid 0.72 g (68% yield). <sup>1</sup>H-NMR (400 MHz, CDCl<sub>3</sub>):  $\delta$  [ppm] 9.69 (s, 2H), 8.19 (s, 2H), 7.87 (d, 2H), 7.18 (d, 2H), 7.12 (dd, 2H). MS (EI): m/z 210 (M<sup>+</sup>).

2,6-Diyl bis(trifluoromethanesulfonate)-anthracene: To a 50 mL two neck round bottom flask charged with magnetic bar was added crude product 1 (420 mg, 2 mmol), then protected under argon, dry dichloromethane (8 mL) and triethylamine (1.4 mL). After cooling to -20 °C, triflic anhydride (0.82 mL, 5 mmol) was slowly added dropwise via syringe. The mixture was stirred for 2 h and then warmed up to room temperature. Dichloromethane (10 mL) was added and the mixture was washed with water (10 mL × 3) and brine (10 mL × 3). The organic layer was separated, dried over Na<sub>2</sub>SO<sub>4</sub> and evaporated under reduced pressure, the crude product was purified by column chromatography (silica, petroleum / dichloromethane) to afford white yellowish solid (550 mg, 58%yield). <sup>1</sup>H-NMR (400 MHz, CDCl<sub>3</sub>):  $\delta$  [ppm] 8.41 (s, 2H), 8.03 (d, 2H), 7.89 (d, 2H), 7.40 (dd, 2H). MS (EI): m/z 474 (M<sup>+</sup>).

2,6-Diphenylanthracene, DPA: To a 100 mL flask, 474 mg (1 mmol) 2, 268 mg (2.2 mmol) phenylo boric acid and Pd(PPh<sub>3</sub>)<sub>4</sub> 63 mg (0.05 mmol) was added under argon. Then 2 mL ethanol, 8 mL toluene and 2mL 2M K<sub>2</sub>CO<sub>3</sub> aqueous solution was added. The whole system was heated to 90 °C and kept overnight. Then the whole system was filtered, the filtrate was washed with triethylamine, dichloromethane, water and ethanol successively, and then further purified by sublimation. DPA was obtained as a yellow solid in a yield of 85% (280 mg). <sup>1</sup>H-

NMR (400 MHz, CDCl<sub>3</sub>): δ [ppm] 8.50 (s, 2H), 8.21 (s, 2H), 8.10 (d, 2H), 7.78 (m, 6H), 7.52 (t, 4H), 7.40 (m, 2H). MS (EI): m/z 330 (M<sup>+</sup>). Elemental analysis calculated for C26H18: C 94.51, H 5.49. Found: C 94.48, H 5.45.

### Instrument Descriptions and Experimental Details.

<sup>1</sup>H-NMR spectra were recorded on a Bruker 400 MHz spectrometer in deuterated chloroform with tetramethylsilane (TMS) as an internal reference. All chemical shifts were reported relative to TMS at 0.0 ppm. TGA was carried out on a Perkin Elmer TGA7 under nitrogen. CV was run on a CHI660C electrochemistry station in THF solution using tetrabutylammonium hexafluorophosphate (Bu<sub>4</sub>NPF<sub>6</sub>) as electrolyte at a scan speed of 100 mVs<sup>-1</sup>, and glassy carbon was used as the working electrode and Pt wire as the counter electrode and ferrocene as inner standard. The UV-vis spectra were obtained on a Jasco V-570 UV-vis spectrometer with solution concentration of 1 × 10<sup>-5</sup> mol/L. X-ray diffraction measurement was performed in reflection mode at 40 kV and 200 mA with Cu Ka radiation using a 2 kW Rigaku D/max-2500 X-ray diffractometer. The films were imaged in air using a Digital Instruments Nanoscope III atomic force microscope operated in tapping mode.

OFET devices were fabricated in top-contact geometry. Thin films were deposited under vacuum on OTS-modified Si/SiO<sub>2</sub> substrates and 20 nm thick gold source and drain electrodes were deposited successively using the shadow masks with width-to-length ratio (W/L, 240µm/30µm) of cal. 8/1. Organic semiconductors were deposited under a pressure of about  $4.0 \times 10^{-4}$  Pa determined by a quartz crystal monitor. OFET characteristics were obtained at room temperature in air on a Keithley 4200 SCS and Micromanipulator 6150 probe station. And the mobility was calculated by using the equation:  $I_{DS} = (W/2L)C_i\mu(V_G-V_T)^2$ .

## Measurements of contact resistance.

DPA-thin film devices are fabricated based on OTS-modified Si/SiO<sub>2</sub> substrate with bottom-gate topcontact geometry. The channel lengths are 50  $\mu$ m, 70  $\mu$ m, 90  $\mu$ m with the same channel width of 1.2 mm. Figure S3 shows the relationship between the R<sub>ON</sub> resistance and channel length at different gate voltages for the DPA-based devices with gold source and drain electrodes. According to the equation in the linear operation regime (V<sub>DS</sub> << V<sub>G</sub>), R<sub>ON</sub>=R<sub>ch</sub>+R<sub>c</sub>=L/WC<sub>i</sub> $\mu$ (V<sub>G</sub>-V<sub>T</sub>)+R<sub>c</sub>, where R<sub>ON</sub> is the ON resistance, R<sub>ch</sub> is the channel resistance and R<sub>c</sub> is the contact resistance,<sup>1</sup> the R<sub>c</sub> can be extracted by measuring the ON resistance from the linear region of the DPA-FET output characteristics. Since W was constant in the measurement, by extrapolating the relationship of  $R_{ON}$  vs L at L=0, the calculated  $R_c$  value is around 0.1 M $\Omega$ .<sup>1b,2</sup> The contact resistance in DPA-thin film transistors is due to the mismatch of the HOMO level of DPA (-5.6 eV) and the work function (-5.1 eV) of gold electrodes as well as structural defects at the interface.

**Table S1.** Summary of the properties of typical anthracene derivatives in comparison with pentacene. Based on the previous studies, the chemical structure of a novel anthracene derivative, DPA, designed for promising semiconductor candidate is shown in the bottom column.

Molecular structure			HOMO (eV)	Eg (eV)	Mobility (cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup> )	Reference
Pentacene			-5.1°	1.8	1-2.3	3
Anthracene			-5.79°	3.9	0.02 <sup>b</sup>	4
BPEA			-5.49°	2.57	0.03~0.73 <sup>b</sup>	5
BNEA			-5.49°	2.5	0.01~0.52 <sup>b</sup>	5
"H" type molecule			-5.4~- 5.5 °	2.5~2. 6	0.2~0.82 <sup>b</sup>	6
2-A	R C C C C C C C C C C C C C C C C C C C	R=H	 -5.09°		0.013 a	7
DH-2A		$R = C_6 H_1$			0.11 ª	
DTAnt	R L S L L S R	R=H		2.8 °	0.063±0.06 a	8
DHTAnt		$R = C_6 H_1$		2.8 °	0.5±0.045 ª	
TVAnt	Los Constant	R=H	-5.42 °	2.55	0.44 <sup>a</sup>	9
HTVAnt		$R=C_6H_1$	-5.2 °	2.59	0.15 ª	
DNVAnt	00-000	-00	-5.54 °	2.71	0.2 ª	10
DPVAnt	R-QQQQ <sup>R</sup>	R=H	-5.4 °	2.6	1.3 <sup>a</sup> 4.3 <sup>b</sup>	3a, 11
DPPVAnt		$R = C_6 H_1$	-5.52 °	2.59	1.28 ª	
Our target molecule: DPA			-5.6 °	3.0	14.8 <sup>a</sup>	Our work

<sup>a</sup> Corresponding to thin film FETs, <sup>b</sup> corresponding to single crystal FETs, <sup>c</sup> all the HOMO levels and bandgaps are obtained from experimental results.



Figure S1. Thermogravimetric analysis of DPA.



**Figure S2.** All the transfer and representative output curves of our 30 transistors included in Fig. 4D separated into four groups according to the mobility distribution: (A), mobilities in the region of 8-10 cm<sup>2</sup> V<sup>-1</sup>s<sup>-1</sup>, B, mobilities in the region of 10-12 cm<sup>2</sup> V<sup>-1</sup>s<sup>-1</sup>, C, mobilities in the region of 12-14 cm<sup>2</sup> V<sup>-1</sup>s<sup>-1</sup>, D, mobilities in the region of 14-16 cm<sup>2</sup> V<sup>-1</sup>s<sup>-1</sup>.



Figure S3. The relationship between  $R_{ON}$  resistance and channel length at different gate voltages for DPA transistors.



Figure S4. Threshold voltage dependence on time.

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